

## **IN THE SPECIFICATION**

Please replace the paragraph beginning at page 6, line 1 with the following:

Referring to FIGS. 5 to 7B, the substrate inspection apparatus 100 preferably includes a laser source 110 for generating a laser beam 20, a detector 120 for detecting a light 30 scattered from a semiconductor substrate 10, an operation unit 130 for analyzing intensities of the scattered light 30, a controller 140 for controlling the operation of the laser source 110, and an image processing unit 150 for receiving an image representing the semiconductor substrate 10 using the intensity of the ~~scattered light 10~~ scattered light 30.